34. A capacitive sensing device formed by a process comprising:

utilizing a substantially transparent substrate; and

using a first patterning process to generate a first plurality of conductive traces above said substantially transparent substrate, said first patterning process generating each of said first plurality of conductive traces having a width such that said capacitive sensing device does not have to be arranged with respect to an underlying image in order to avoid deleterious obstruction of said underlying image by said first plurality of conductive traces, said underlying image is separate from said capacitive sensing device, wherein said capacitive sensing device is formed separately from active components of an information display.

35. The capacitive sensing device as described in claim 34, wherein said first patterning process is selected from the group consisting of:

a lithographic process, a printing process, electron beam lithography, screen printing, inkjet printing, offset printing, electroplating, stamping, and LIGA.

36. The capacitive sensing device as described in claim 34, further comprising:

using a second patterning process to generate a second plurality of conductive traces above and coupled to said substantially transparent substrate.

37. The capacitive sensing device as described in claim 36, wherein said second patterning process generates each of said second plurality of conductive traces has a width such that said capacitive sensing device does not have to be arranged with respect to said underlying image in order to avoid deleterious obstruction of said underlying image by said second plurality of conductive traces.

38. The capacitive sensing device as described in claim 36, wherein said first patterning process and said second patterning process are each selected from the group consisting of:

a lithographic process, a printing process, electron beam lithography, screen printing, inkjet printing, offset printing, electroplating, stamping, and LIGA.

39. The capacitive sensing device as described in claim 36, wherein said first plurality of conductive traces and said second plurality of conductive traces are substantially orthogonal to each other.

40. The capacitive sensing device as described in claim 36, wherein said first plurality of conductive traces or said second plurality of conductive traces comprises at least one layer of substantially opaque material.

41. The capacitive sensing device as described in claim 34, further comprising:

depositing an insulating material above at least a portion of said first plurality of conductive traces.

42. The capacitive sensing device as described in claim 41, wherein said insulating material is substantially transparent.

43. The capacitive sensing device as described in claim 34, wherein said substantially transparent substrate is a component of said information display device.

44. The capacitive sensing device as described in claim 34, wherein said substantially transparent substrate is selected from a group consisting of:

a glass, a plastic, and a crystalline material.

45. The capacitive sensing device as described in claim 34, wherein said first plurality of conductive traces is formed of at least one layer of material that is substantially opaque.

46. The capacitive sensing device as described in claim 34, wherein said first plurality of conductive traces is formed of at least one layer of material that is substantially non-reflective.

47. The capacitive sensing device as described in claim 34, further comprising:

generating a landing pad region above said substantially transparent substrate for coupling a sensing circuit component to said substantially transparent substrate.

48. The capacitive sensing device as described in claim 47, wherein said generating said landing pad region is performed during said first patterning process or said second patterning process.

49. The capacitive sensing device as described in claim 34, wherein each of said first plurality of conductive traces has a width less than approximately 12 micrometers.

50. The capacitive sensing device as described in claim 34, wherein each of said first plurality of conductive traces has a width such that each of said first plurality of conductive traces is not required to be formed of a substantially transparent material.

51. The capacitive sensing device as described in claim 34, wherein each of said first plurality of conductive traces has a width less than a pixel width of said underlying image.

52. The capacitive sensing device as described in claim 34, wherein each of said first plurality of conductive traces is a capacitive sensing element.

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